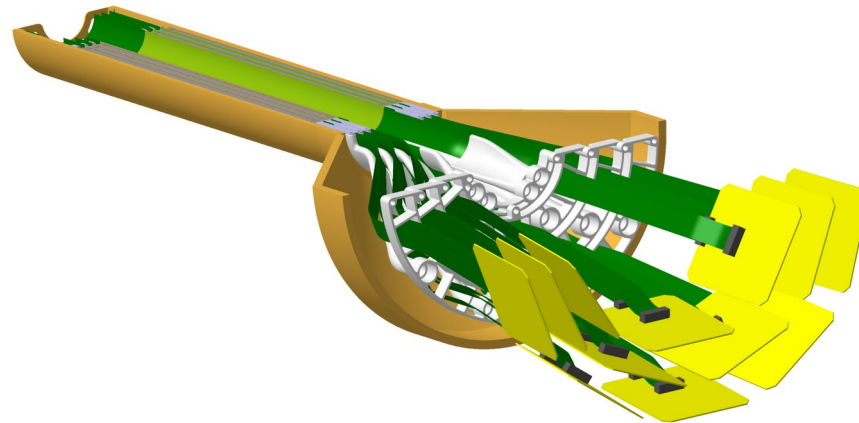


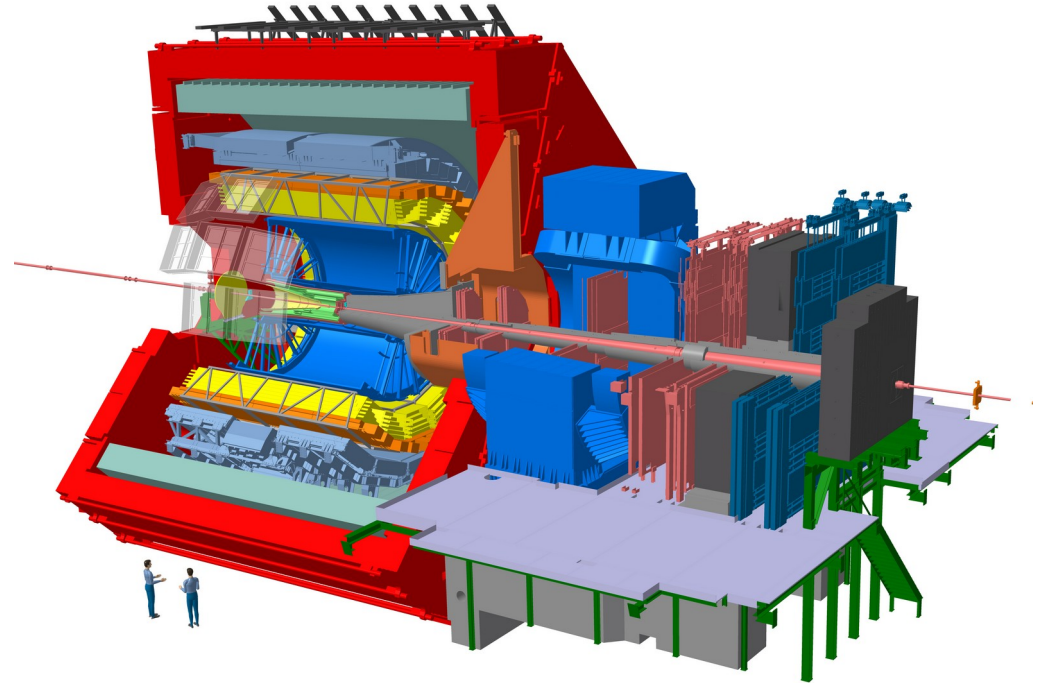
ITS3: next ALICE upgrade of the Inner Tracking System for LHC Run 4

Filip Krizek, NPI CAS
for the ALICE Collaboration

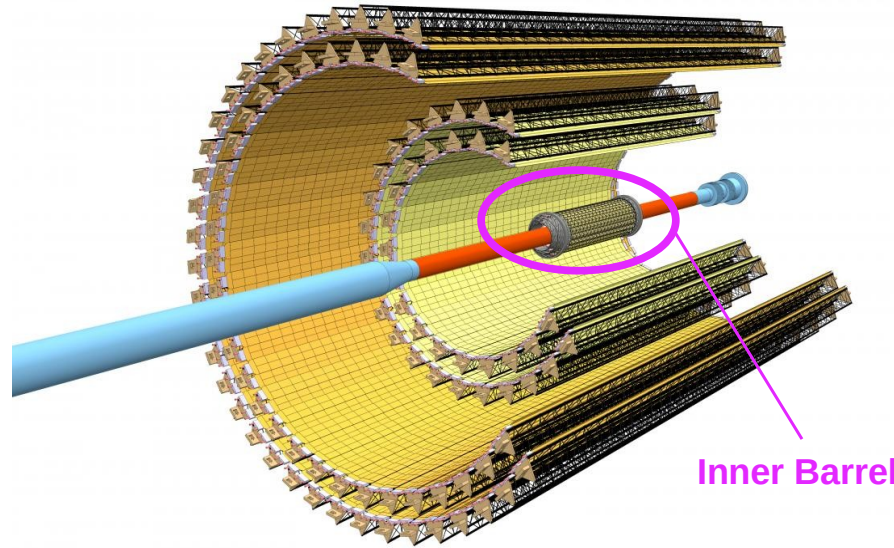


ALICE in LHC Run 3 and Run 4

- **ALICE Physics goals for Run 3 & 4**
 - low- p_T open HF hadrons and quarkonia
 - low-mass dielectrons
 - light nuclei, antinuclei and hypernuclei
- **Key Run 3 upgrade:**
Inner Tracking System (ITS2)
- **Follow up upgrade in Run 4:**
Inner barrel of ITS (ITS3)
 - installation 2026 - 2028
 - in operation 2029 - 2032



Inner Tracking System in Run 3

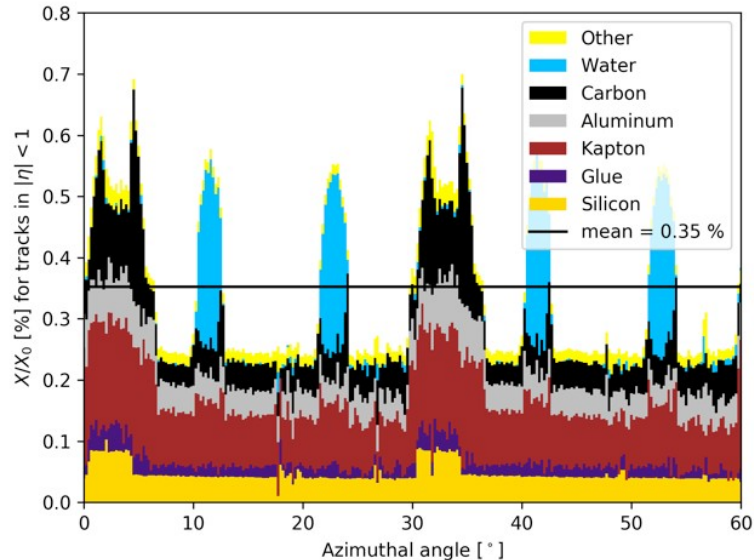
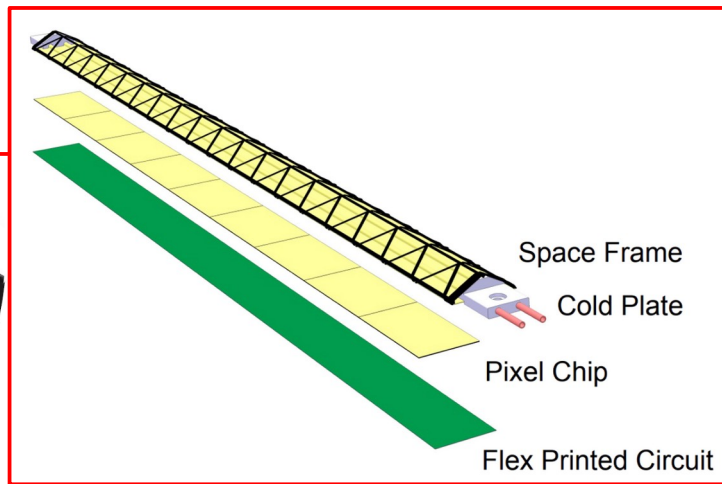
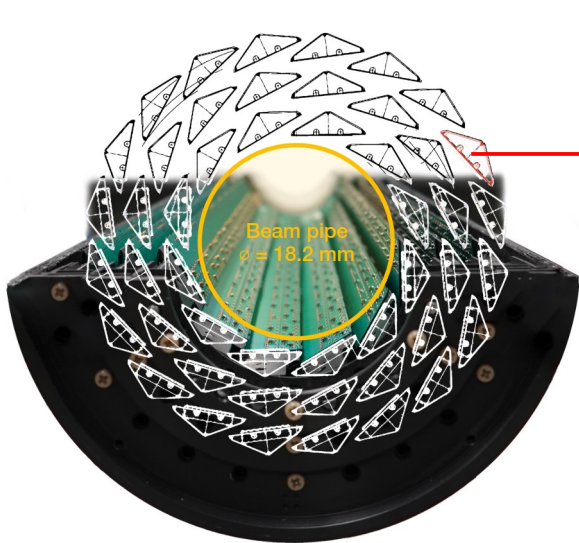


7 layers of Monolithic Active Pixel Sensors (MAPS)

	Layers	Radii (mm)	X_0 /layer
Inner Barrel	3	22 - 42	0.35%
Outer Barrel	4	194 - 395	1.1%

More details in talk by Andrea Sofia Triolo from Mon 16th Oct

Material budget considerations for the Inner Barrel of ITS

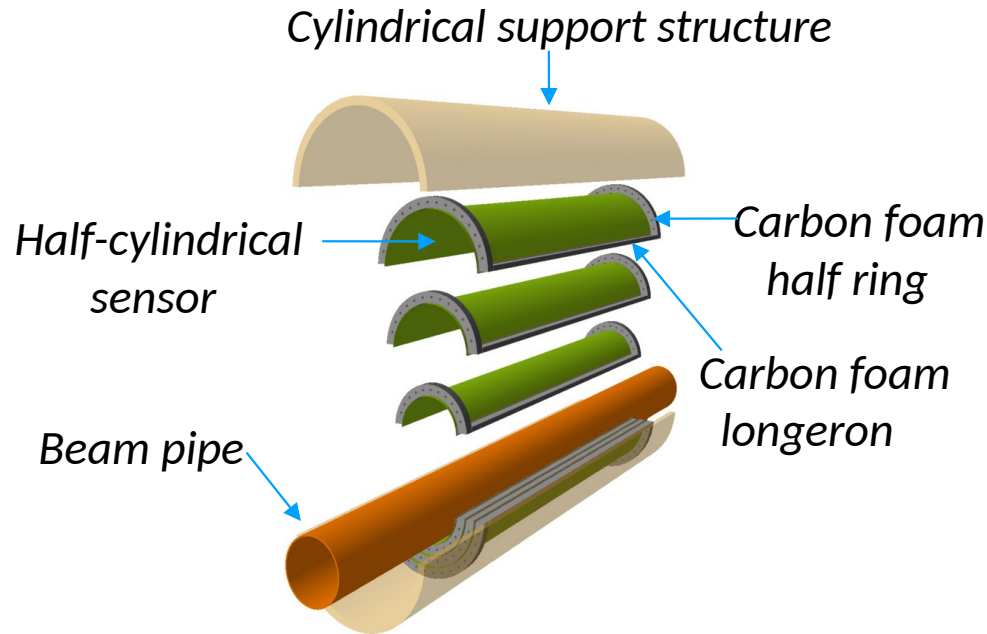


ITS Inner Barrel has 0.35% X_0 /layer but Si makes 1/7th of the total only

Is it possible to further reduce material budget of the inner ITS layers?

- Removal of water cooling → reduce power consumption & move sensor periphery to chip edge
- Removal of circuit board → integrate power and data buses on the chip
- Removal of mechanical support → utilize stiffness of **large size, bent Si wafers**

Inner Barrel of ITS for Run 4 (ITS3)



ITS3 will comprise 6 chips only!

Sensor length 266 mm x width 55 / 74 / 93 mm

Thickness $\leq 50 \mu\text{m}$

Radial position **18 / 24 / 30 mm**

Mechanical support by carbon foam spacers

Material budget 0.05% X_0 /layer

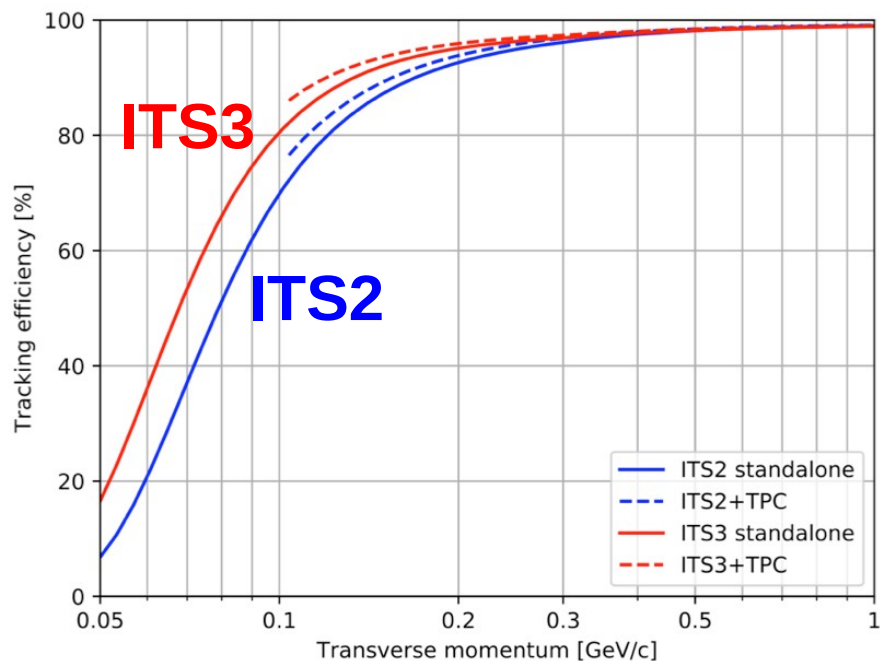
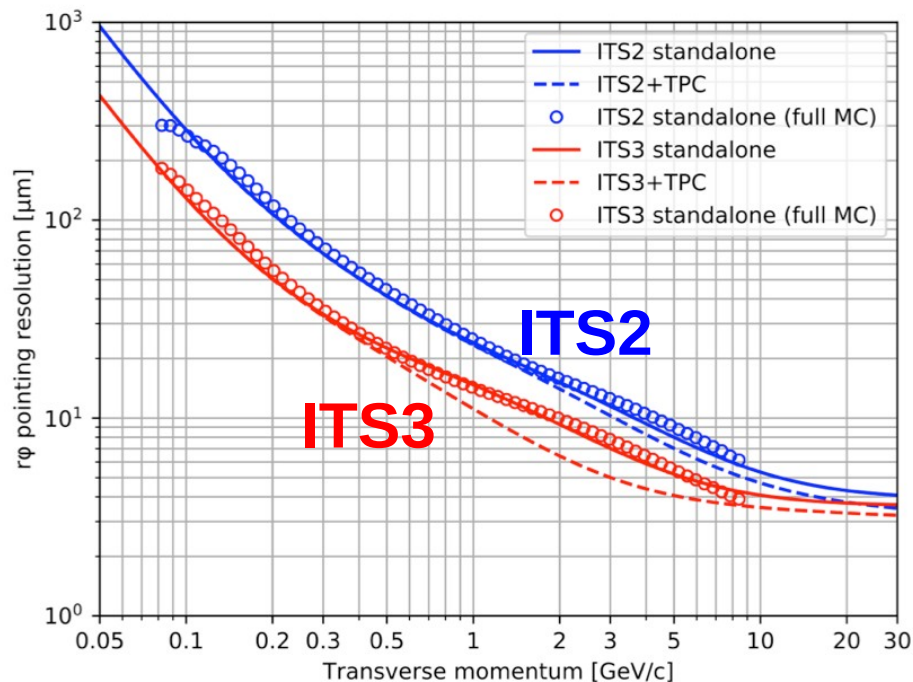
MAPS produced by **65 nm CMOS** process

1D stitching on 300 mm wafers

Spatial resolution requirement $5 \mu\text{m}$

Expected TID 10 kGy & NIEL $10^{13} \text{ 1 MeV } n_{\text{eq}} / \text{cm}^2$

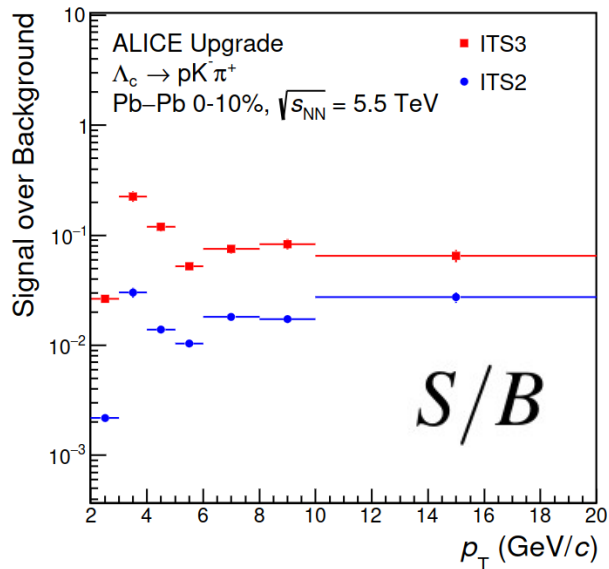
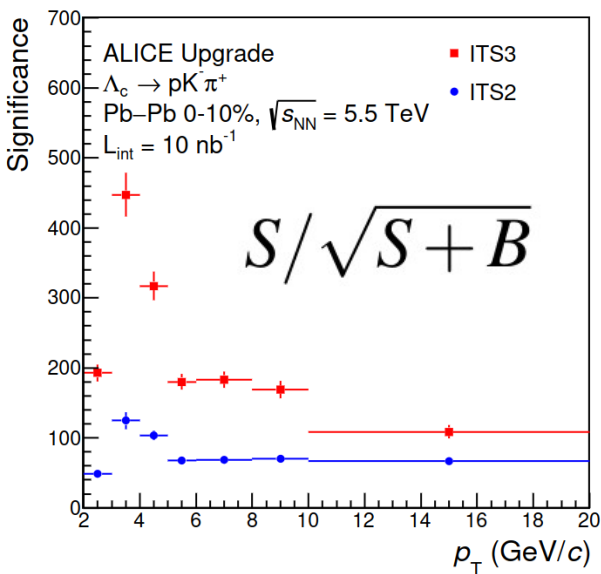
Gain in performance with ITS3



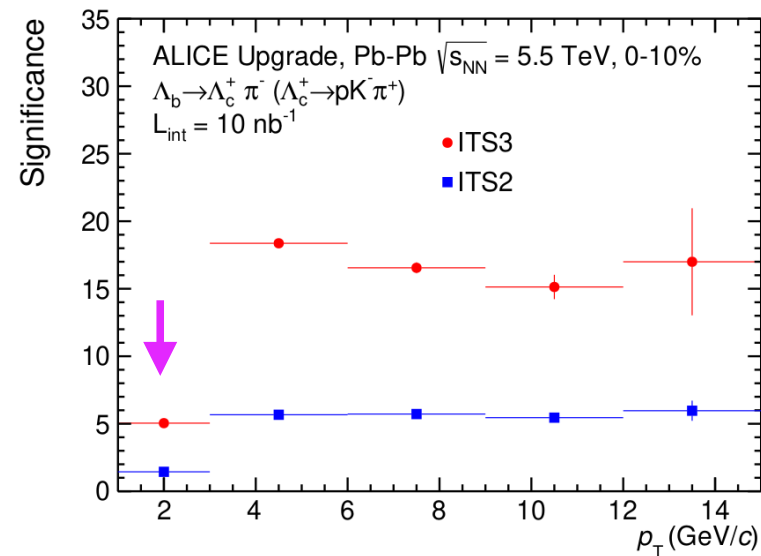
- Improvement in pointing resolution by a factor of 2 over all momenta
- Increase of tracking efficiency for low- p_T particles and extension of the low- p_T reach

Low- p_T heavy-flavor baryons with ITS3

$$\Lambda_c^+ \rightarrow p K^- \pi^+ \quad (c\tau \sim 59 \mu\text{m})$$



$$\Lambda_b^0 \text{ via non-prompt } \Lambda_c^+ \quad (c\tau \sim 369 \mu\text{m})$$

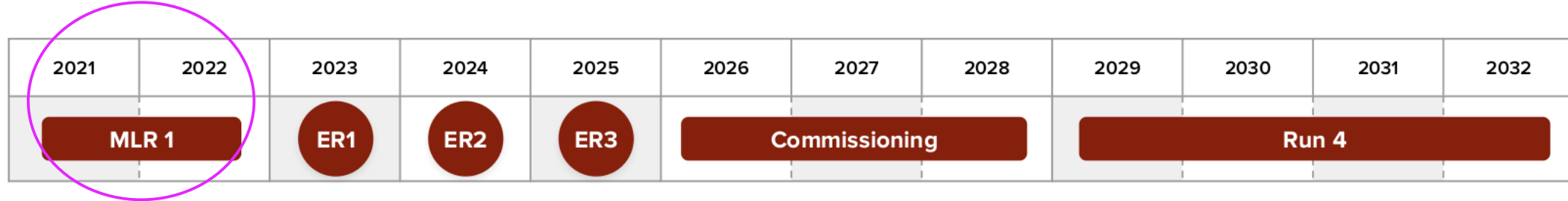


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ITS3 R&D lines

- **Sensor design in 65 nm CMOS technology**
- **Bending of thin silicon sensors & their characterization**
- **Mechanical support**
 - Development of assembly procedure
 - Study of carbon foam support structure
- **Air cooling**

Sensor Design

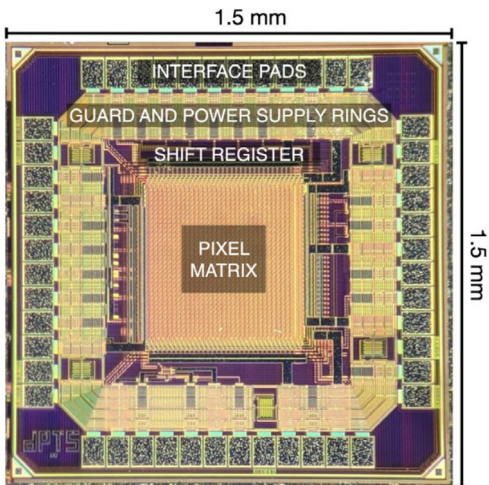


Multi Layer Reticle 1 (MLR1):

- Concentrated effort ALICE ITS3 together with CERN EP R&D
- 3 process variants:
 - *DPTS – Digital Pixel Test Structure*
 - *APTS – Analog Pixel Test Structure*
 - *Circuit Exploratoire 65 nm*

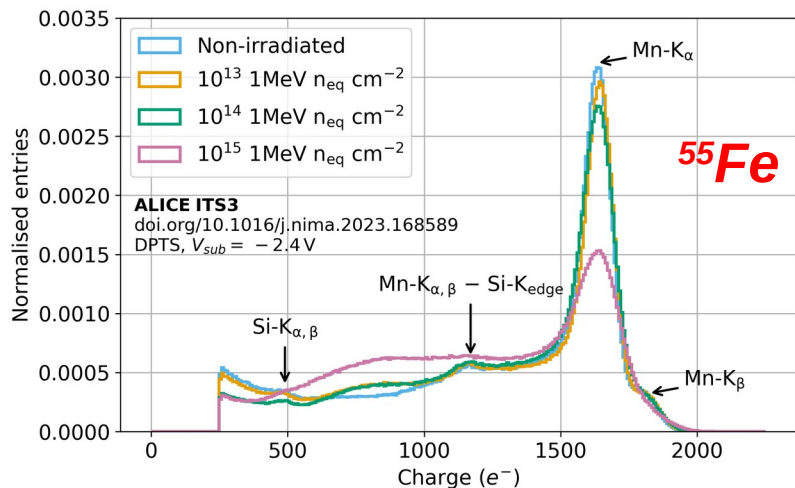
More details in talk by Anna Villani on Wed 18th Oct at 11:30

Characterization of DPTS



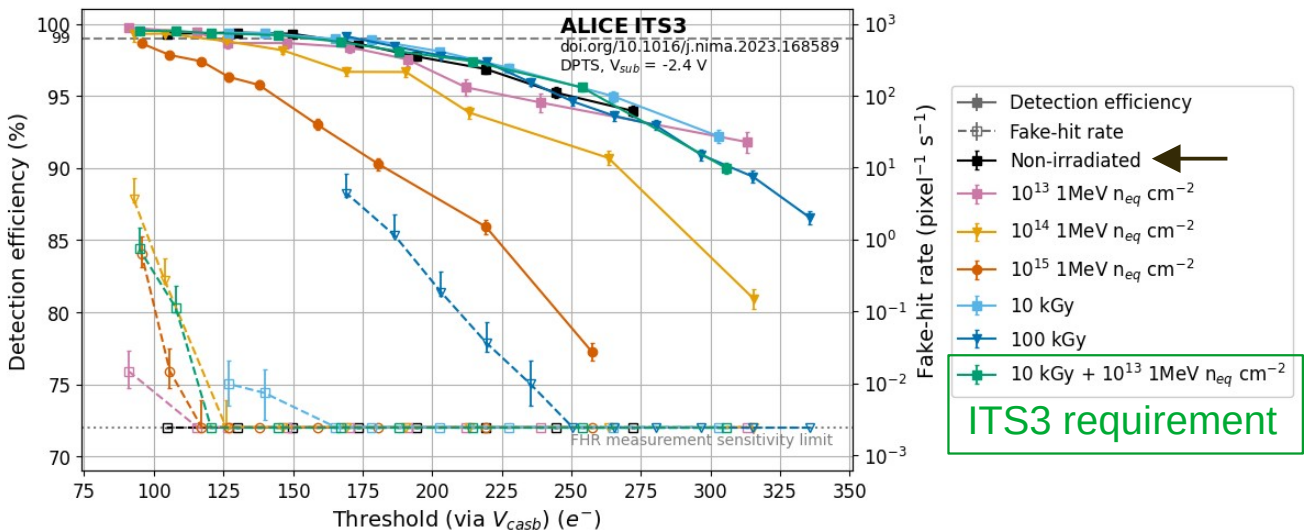
- DPTS 32x32 pixels
- Pixel pitch 15 μm
- Performance of in-pixel front end

ALICE ITS, NIM A 1056 (2023) 168589

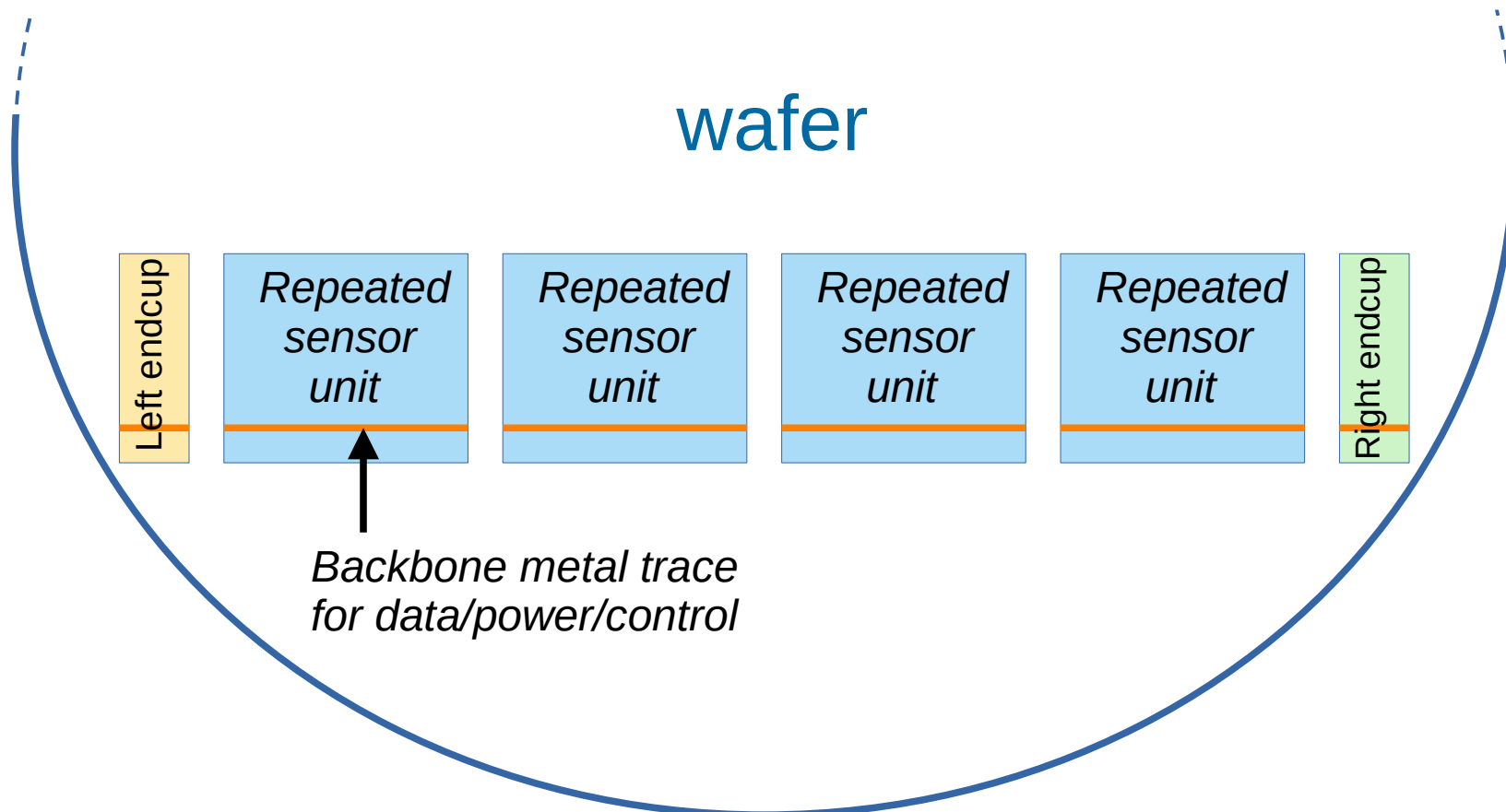


DPTS is sufficiently radiation hard for ITS3

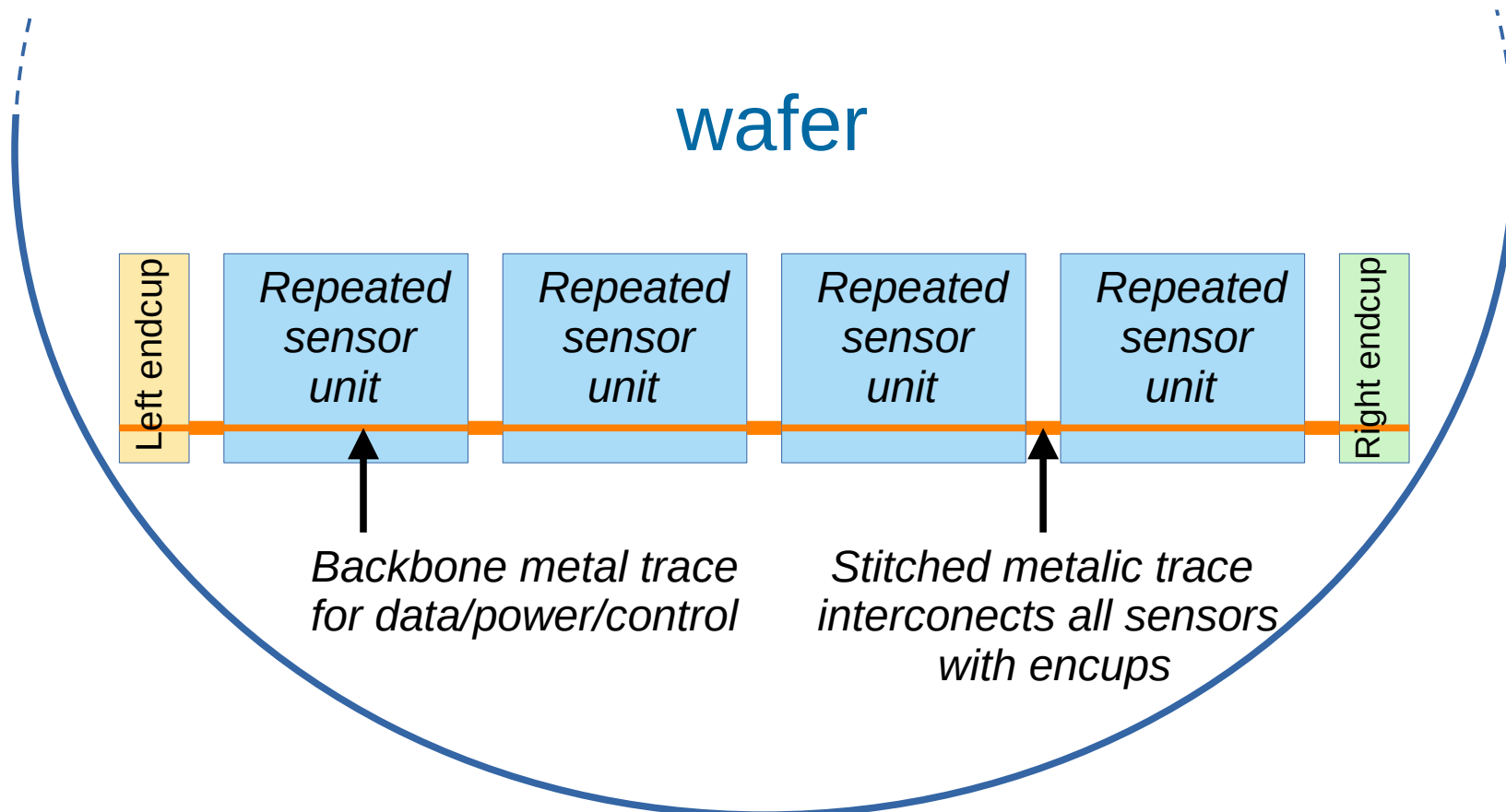
More details in talk by Anna Villani on Wed 18th Oct at 11:30



Stitching in nutshell



Stitching in nutshell



Exploration of sensor stitching on 300 mm wafers in Engineering Round 1

2021	2022	2023	2024	2025	2026	2027	2028	2029	2030	2031	2032
MLR 1		ER1	ER2	ER3	Commissioning			Run 4			

ER1 targets to explore:

- Stitching in one direction for metal traces of power and data buses
- Production yield
- Power distribution and consumption
- Readout over long distances (26 cm)
- Pixel architecture

ER2: final sensor prototype

ER3: final sensor production



Stitching on 300 mm wafers
for 65 nm CMOS technology

Monolithic Stitched Sensors

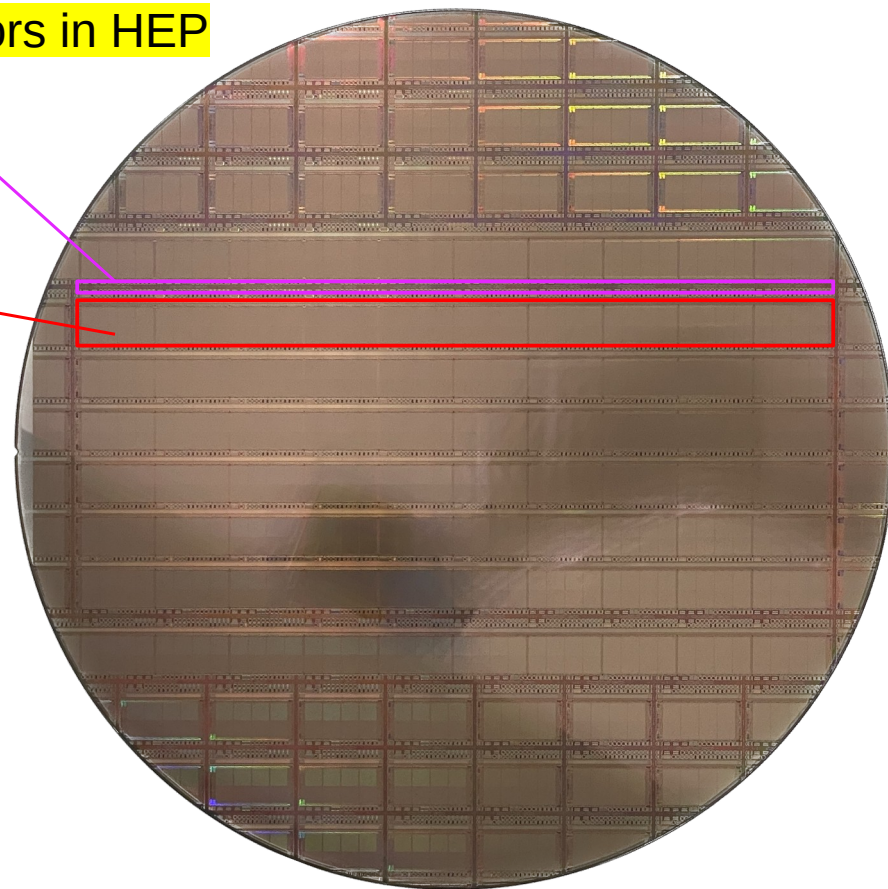
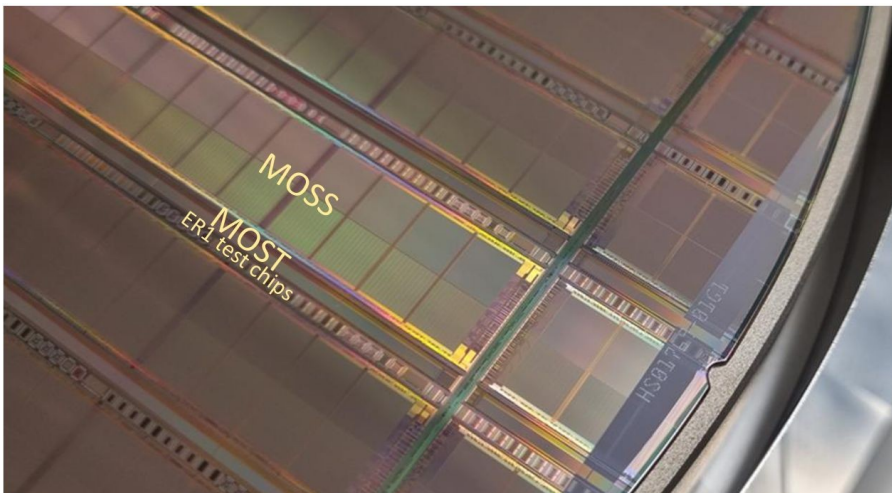
First stitched sensors in HEP

Monolithic Stitched sensor with Timing (MOST)

- Size: 2.5 x 259 mm, 0.9 MPixel, digital readout

Monolithic Stitched Sensor (MOSS)

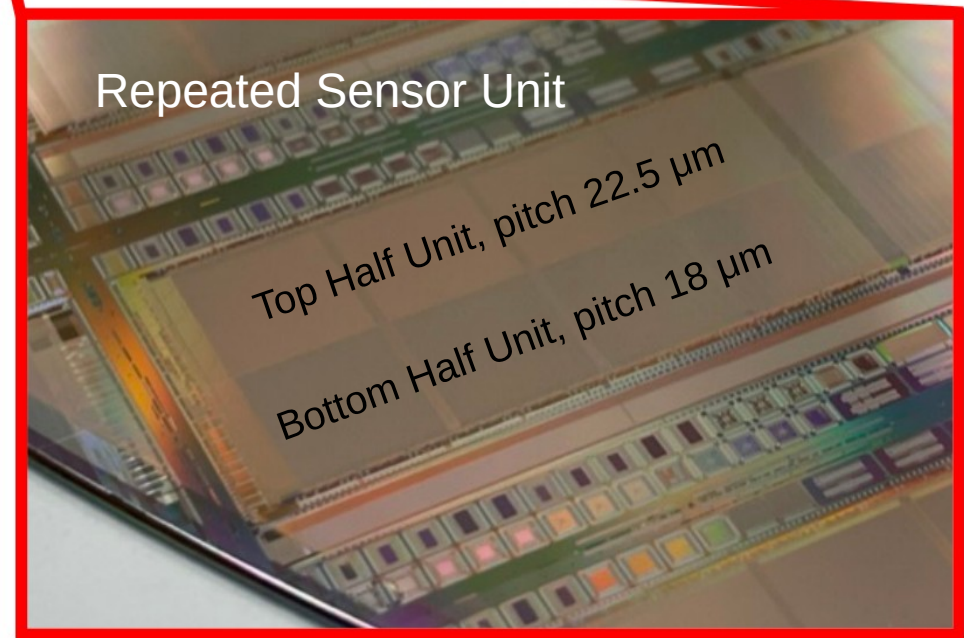
- Size: 14 x 259 mm, 6.72 MPixel, digital readout



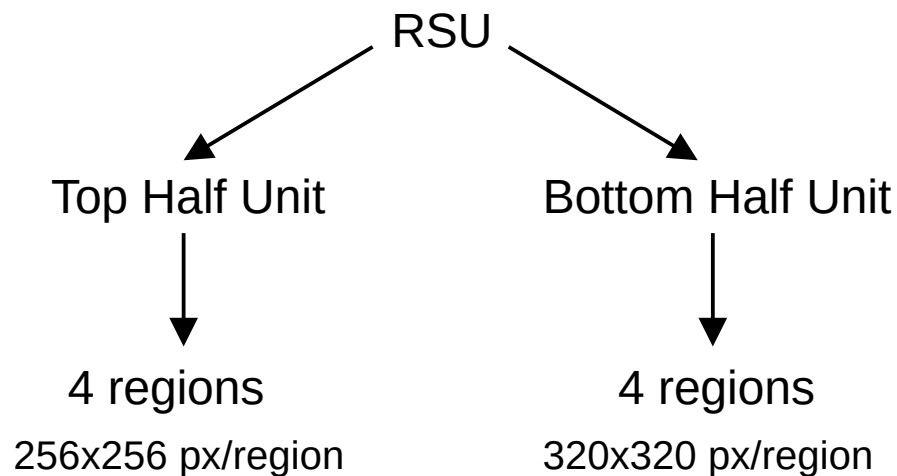
ER1 wafer \varnothing 300 mm

MOSS = Monolithic Stitched Sensor

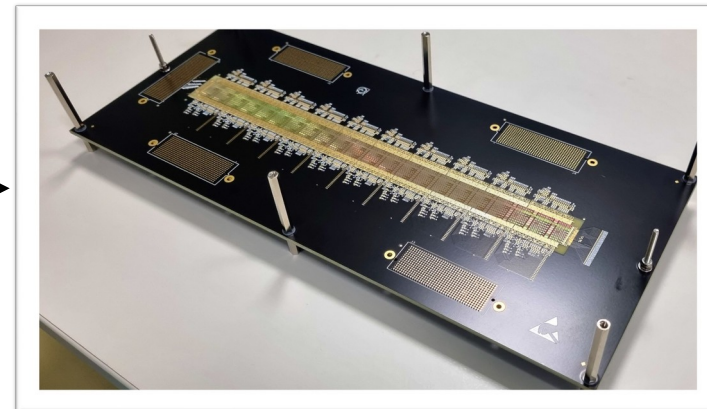
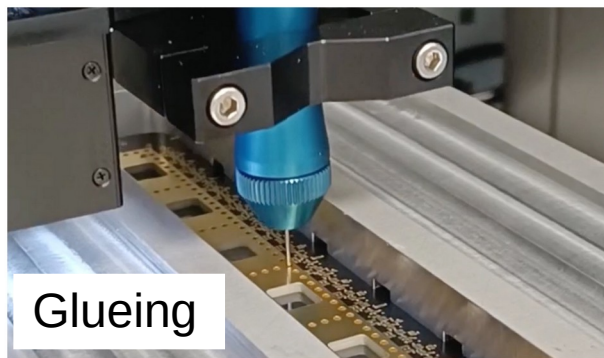
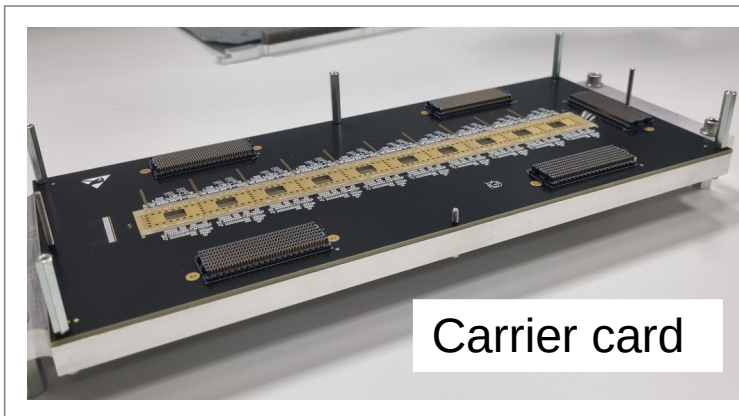
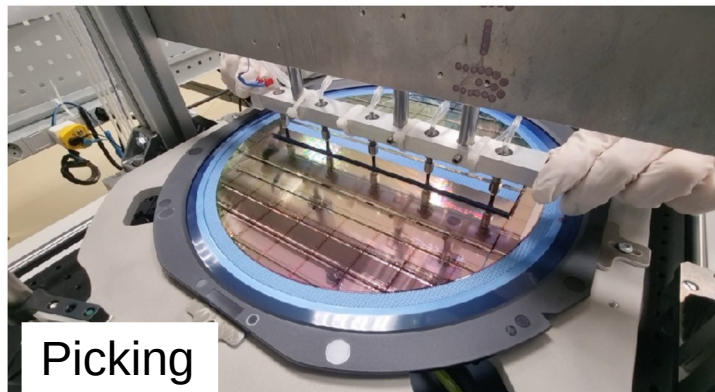
6.72 MPixel



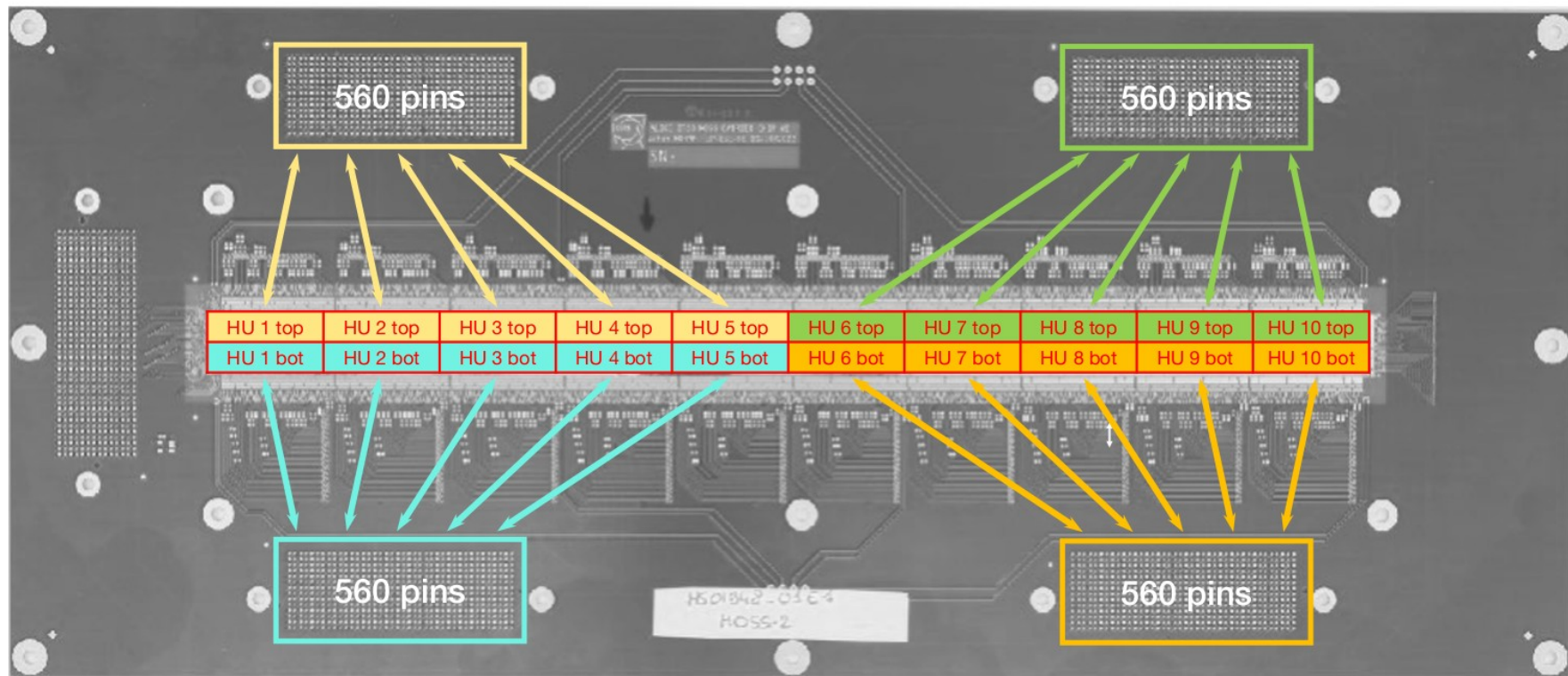
10 Repeated Sensor Units (RSU)



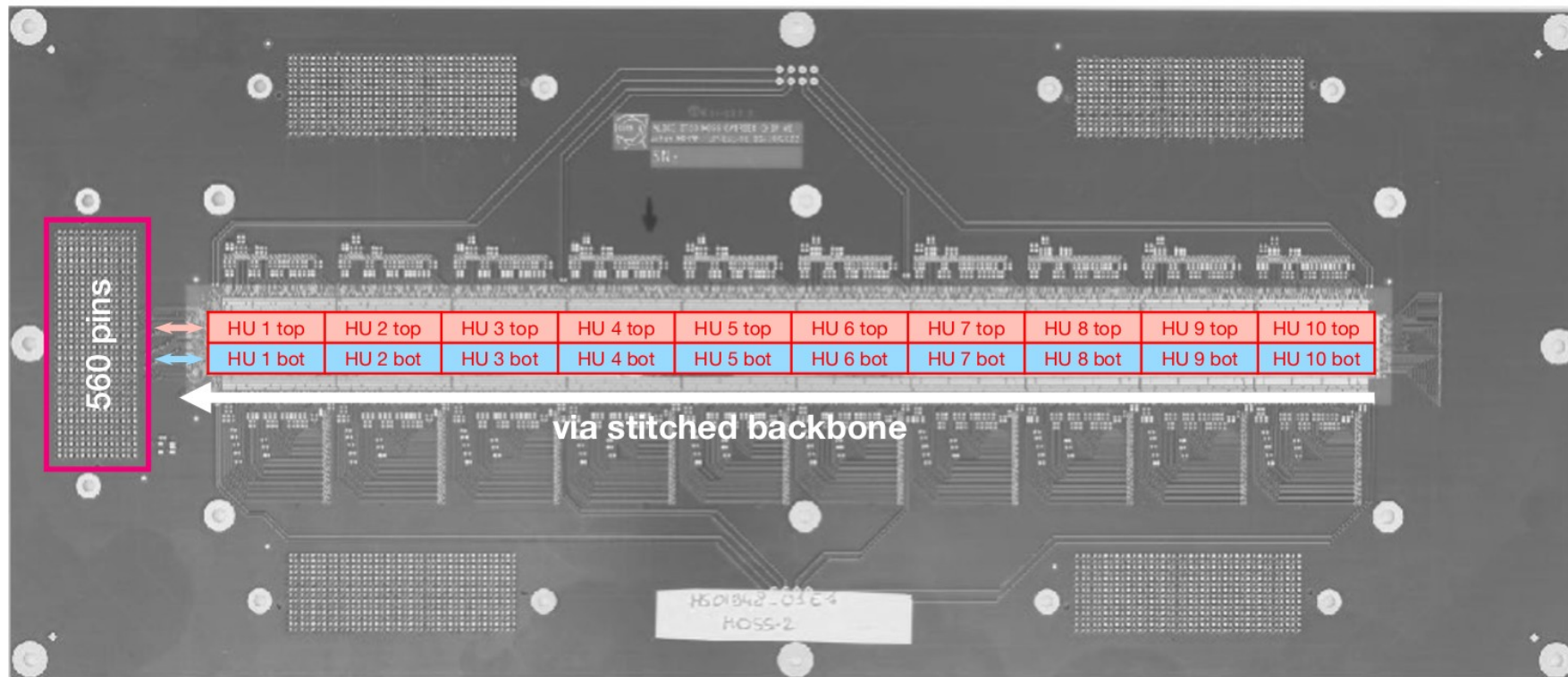
Assembling chip carrier card with MOSS



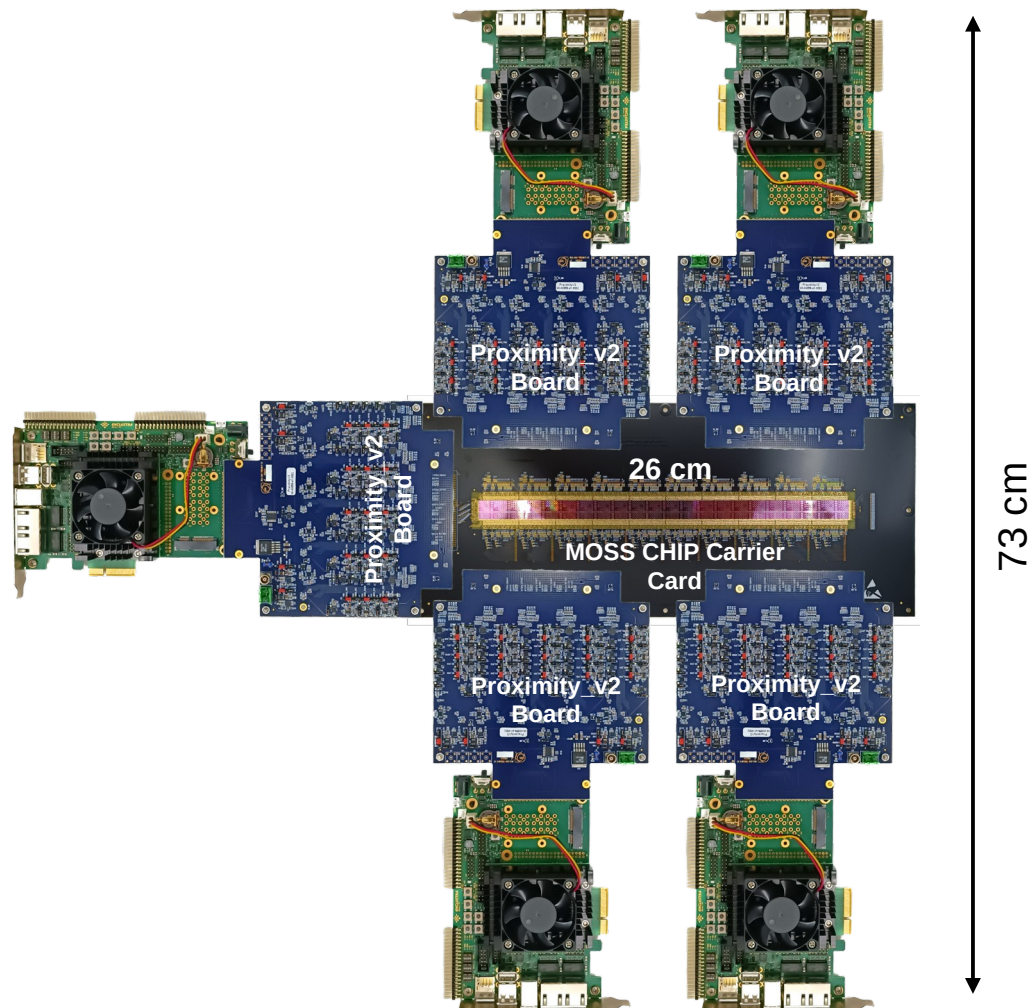
MOSS carrier card



MOSS carrier card



Full MOSS chip test system concept



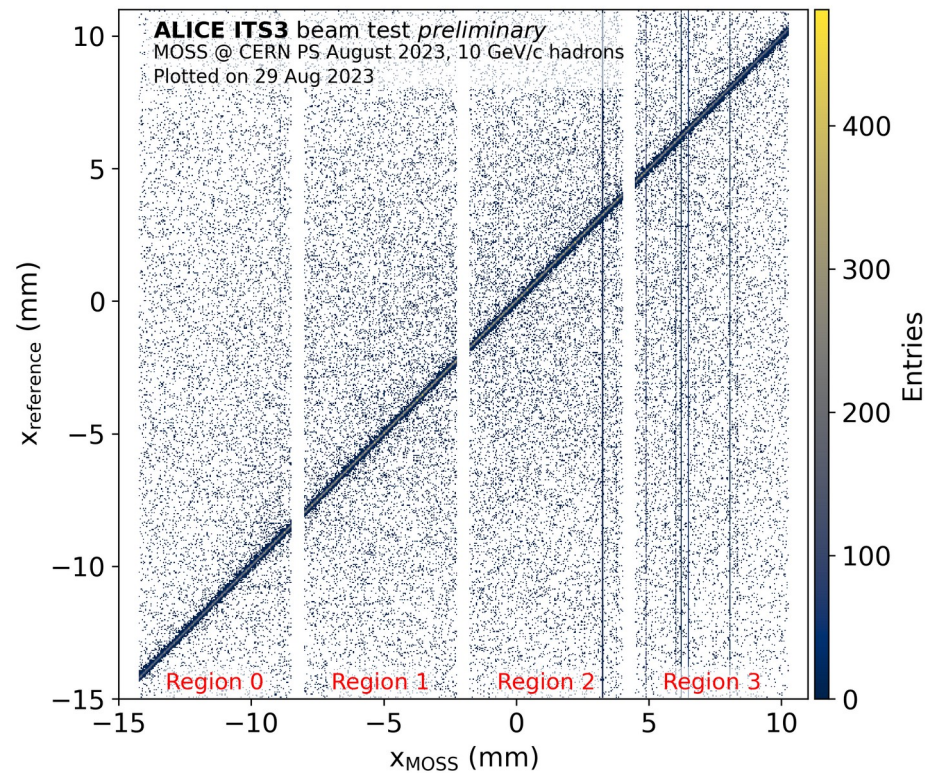
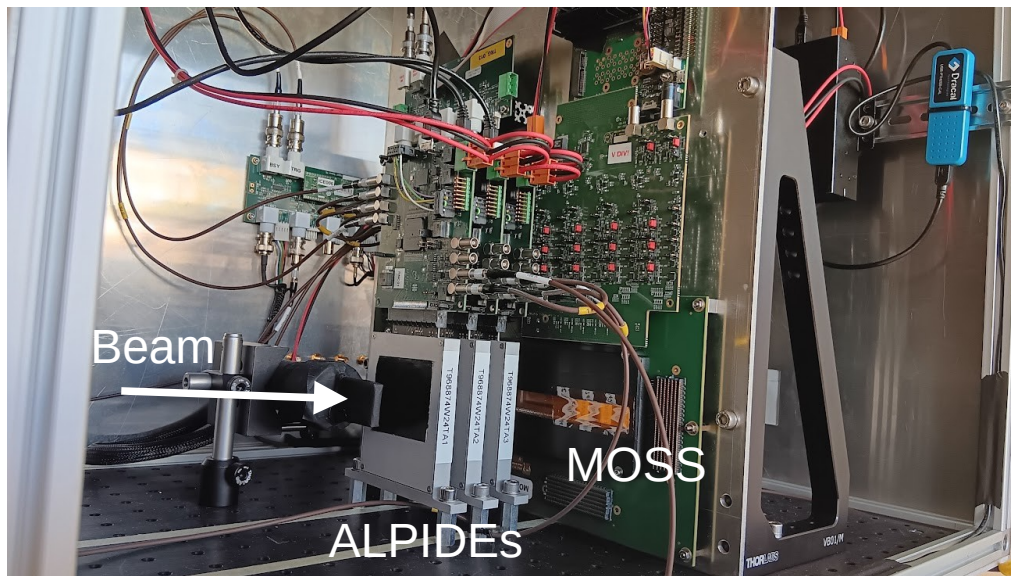
The concept foresees 3 different cards.

- **MOSS-CHIP carrier card**
2800 pads
- **5x Proximity Board**
1 card x 4 quadrants + 1 for stitched backbone supply of power, control, readout, ADCs
- **5x automation and readout modules**
steers the proximity boards and interfaces the sensor control and readout with a computer.

Ongoing tests:

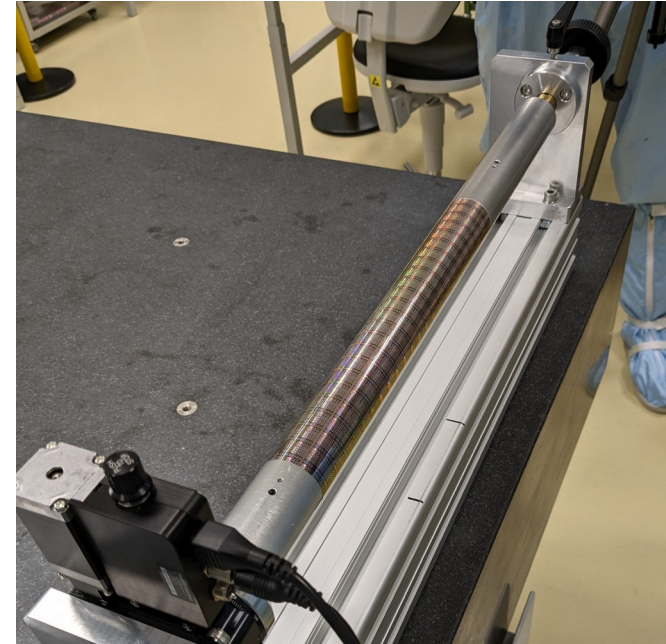
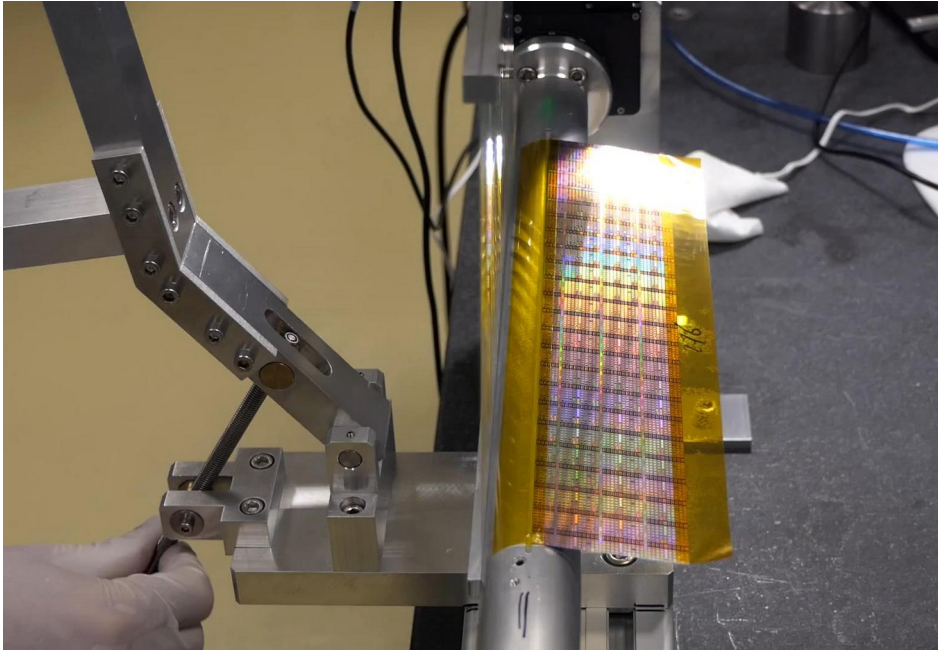
- resistance
- power ramps
- test beams

MOSS chip in test beam

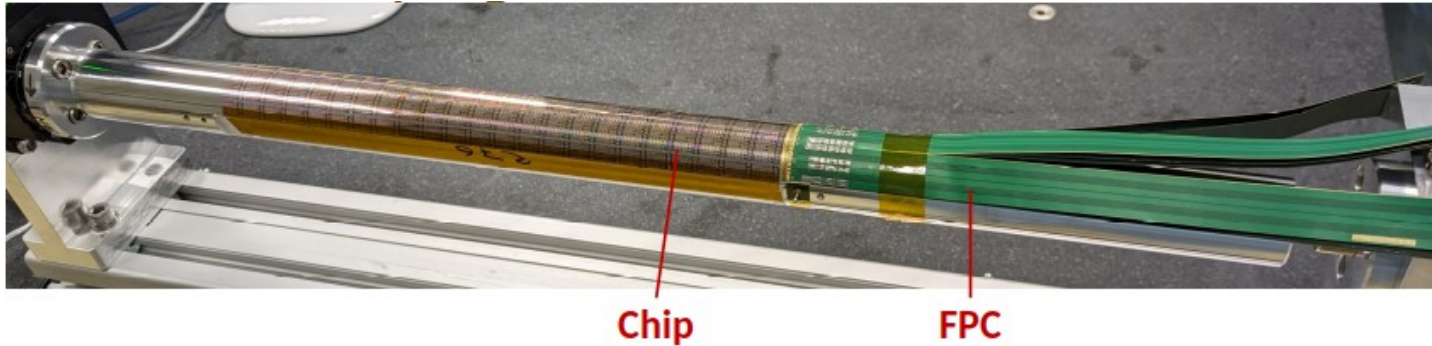


Practicing ITS3 assembly

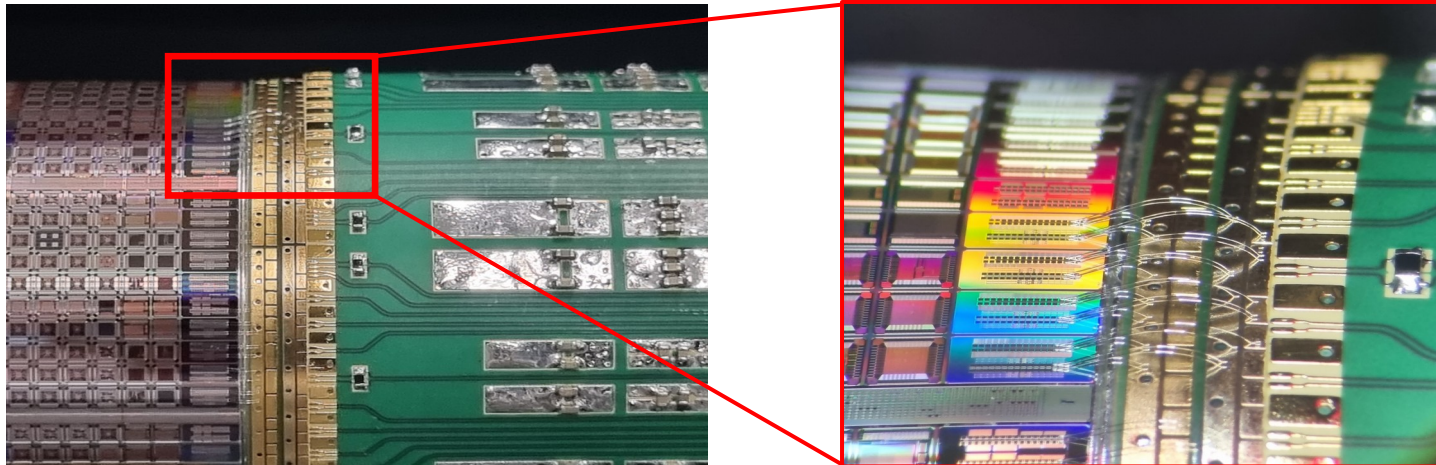
Bending full scale chip, 50 μm thick to radius 19 mm



Practicing ITS3 assembly



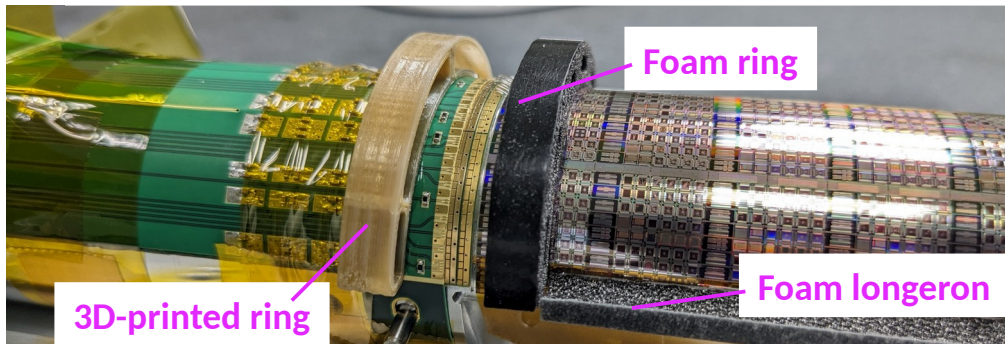
*Aligning FPC
and the sensor*



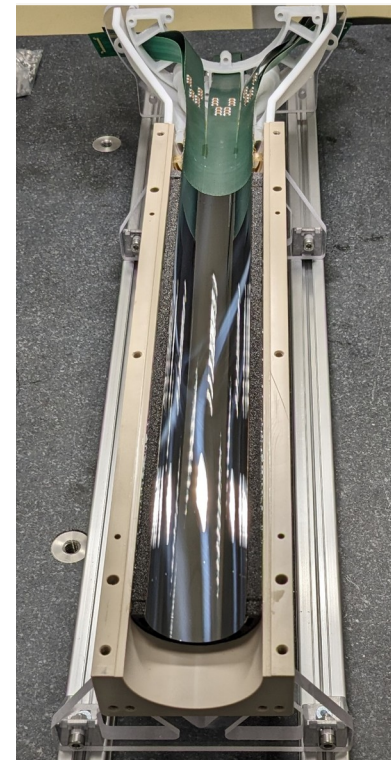
*Bonding the
curverd sensor*

Practicing ITS3 assembly

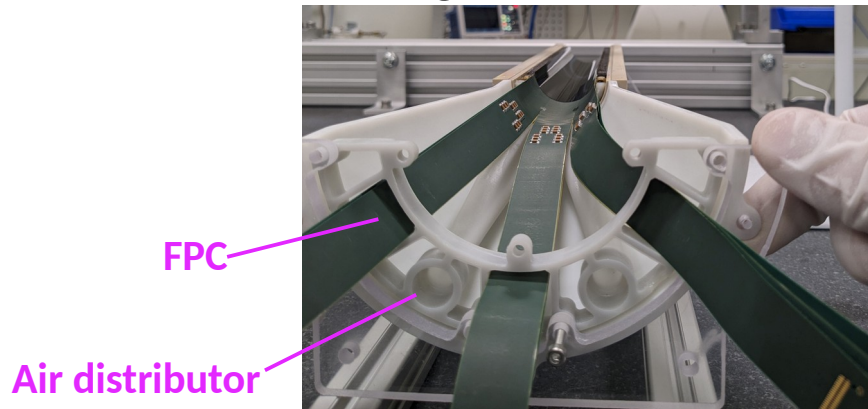
Gluing of foams and additional supports



Assembled first layer of ITS3

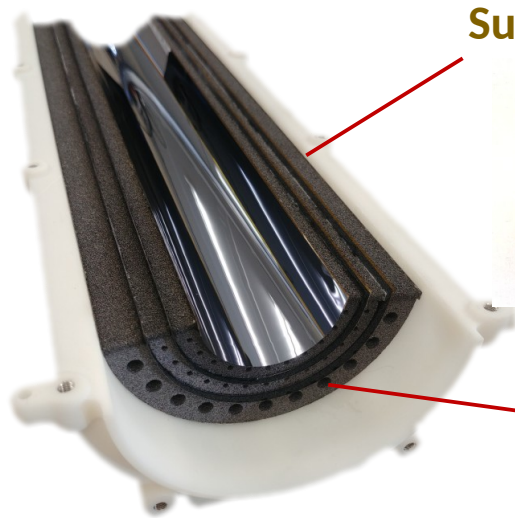


Gluing of the air distributor



Mechanics and cooling solutions

- Limited dissipated power \Rightarrow **air cooling** at ambient temperature
- Low material budget \Rightarrow **carbon foam** used as **support** and **heat exchanger**



Support



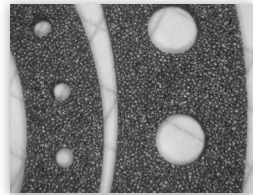
ERG Carbon

@Duocel

$$\rho = 0.045 \text{ kg/dm}^3$$

$$k = 0.033 \text{ W/m}\cdot\text{K}$$

Support & cooling



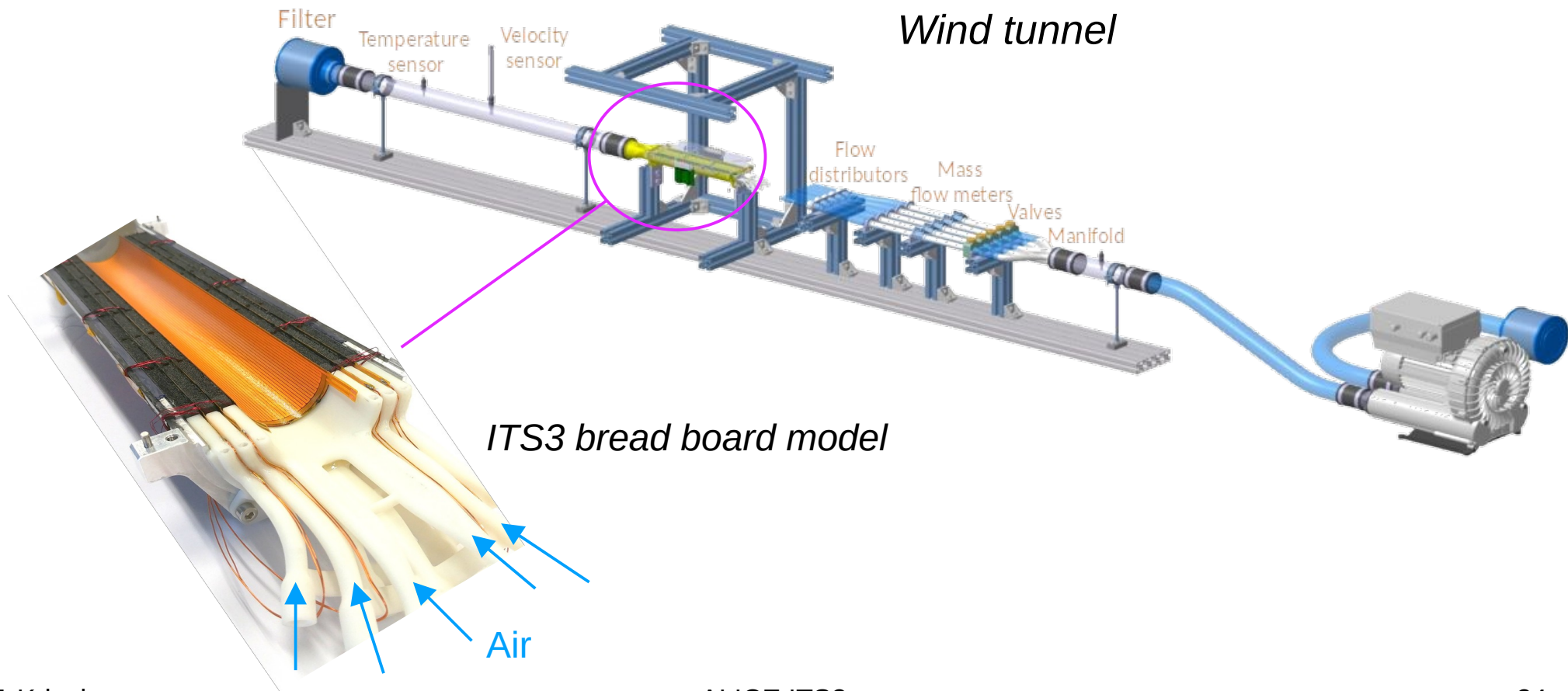
K9

$$\rho = 0.2\text{-}0.26 \text{ kg/dm}^3$$

$$k = >17 \text{ W/m}\cdot\text{K}$$

Higher thermal conductivity
but also higher density

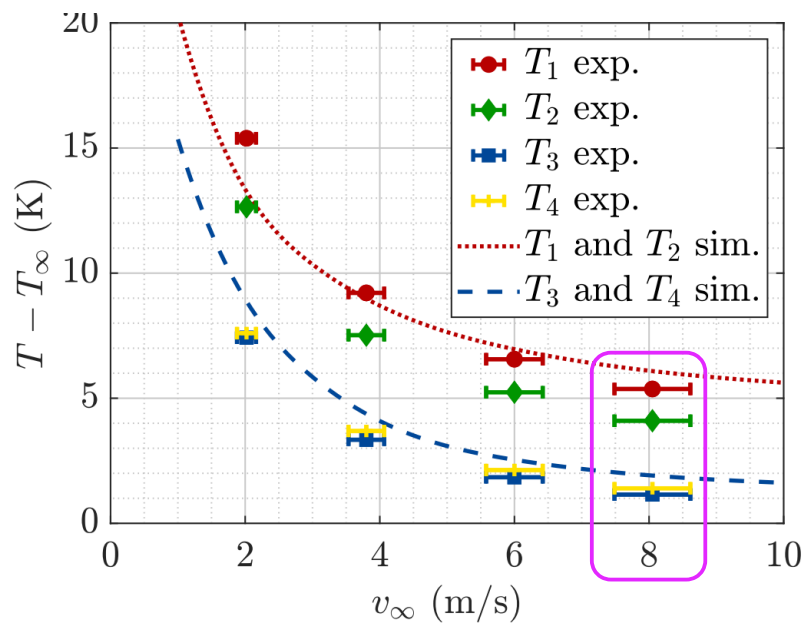
Thermal and mechanical stability tests



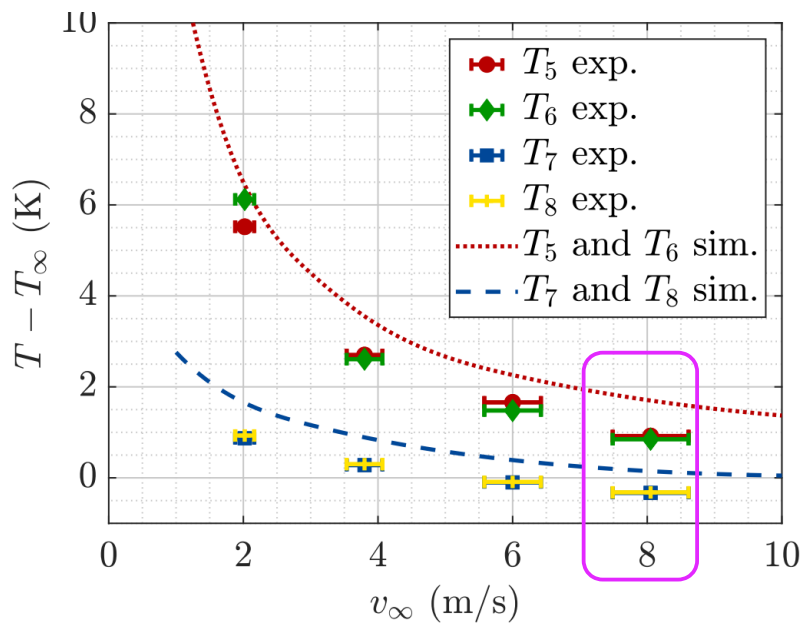
Air cooling



Locations of temperature sensors



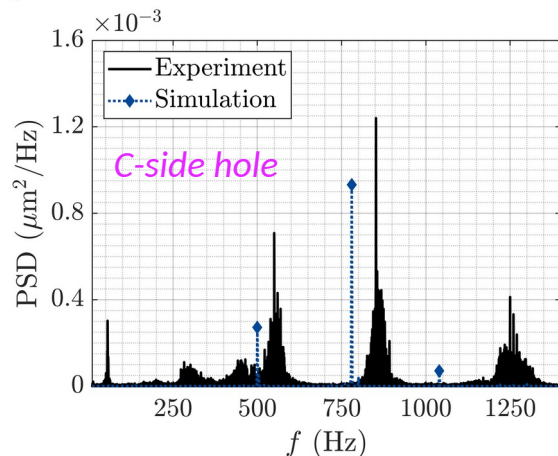
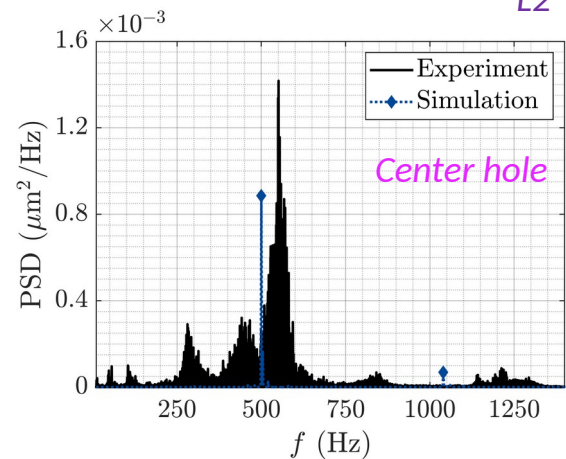
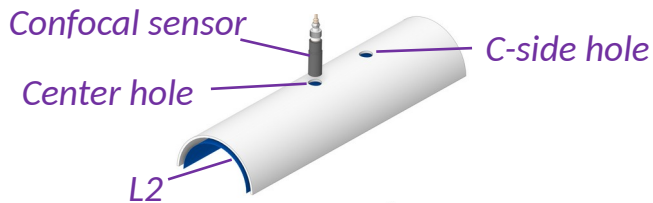
(b) Layer 0 - Endcap



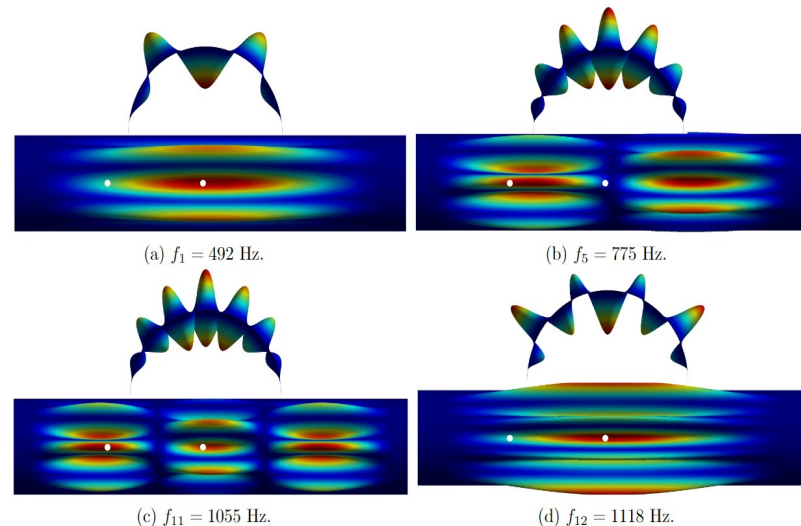
(c) Layer 0 - Matrix

- Sensor temperature must stay $< 30^\circ\text{C}$ \Rightarrow 8 m/s room temperature air flow needed
- Good agreement with Computational Fluid Dynamics model

Vibrational tests



Power spectral density of the displacements of Layer 2

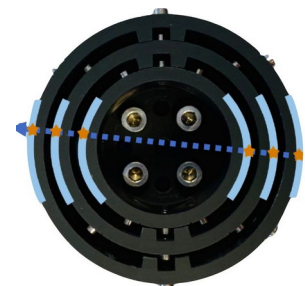
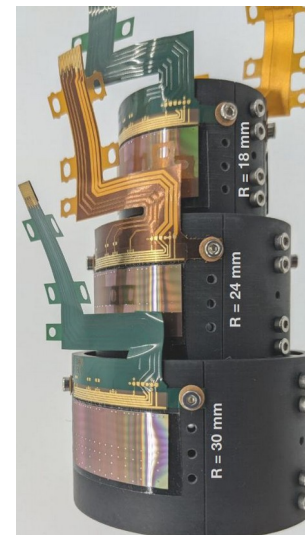
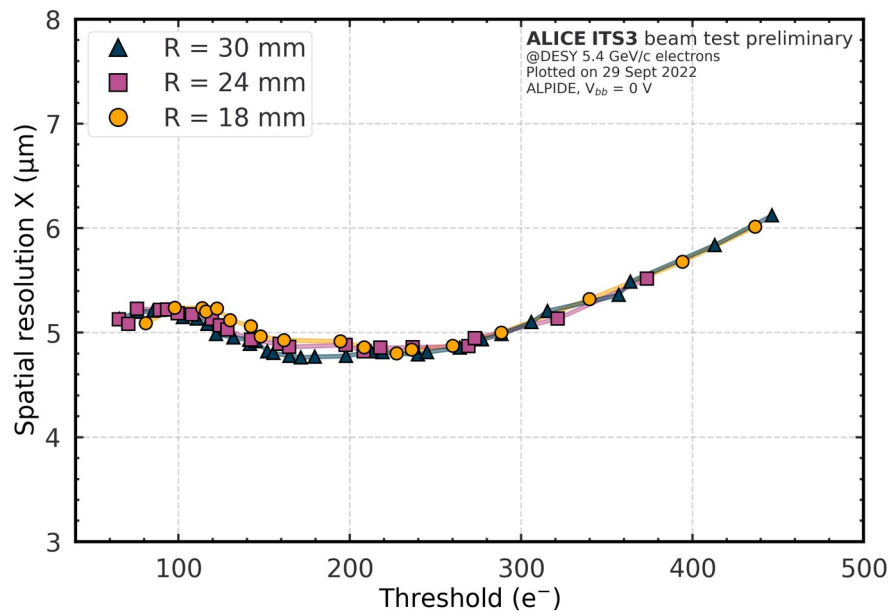
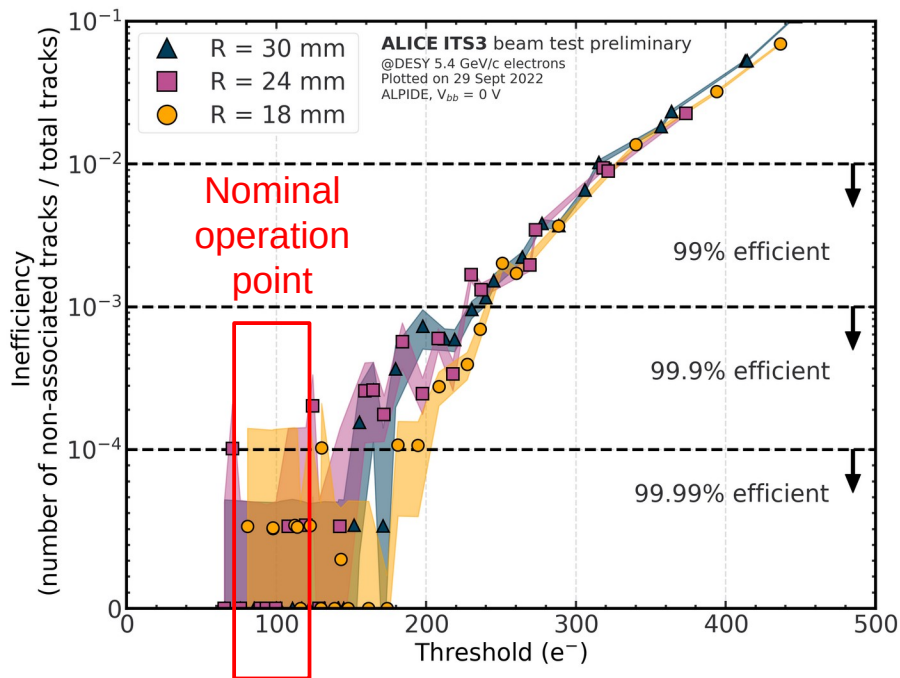


Side and top view of natural frequencies of Layer 2.

- First natural frequency of L2 with integrated heaters 500 Hz
- Simulation by Computational Fluid Dynamics model with decoupled fluid-structure interaction
- Displacements caused by the air flow $< 0.5 \mu\text{m}$

Characterization of bent sensors

- μ ITS3: 6 ALPIDE chips bent to the same radii as ITS3 layers
- Efficiency and spatial resolution are consistent with flat ALPIDE



See also ALICE ITS, NIM A 1028 (2022) 166280

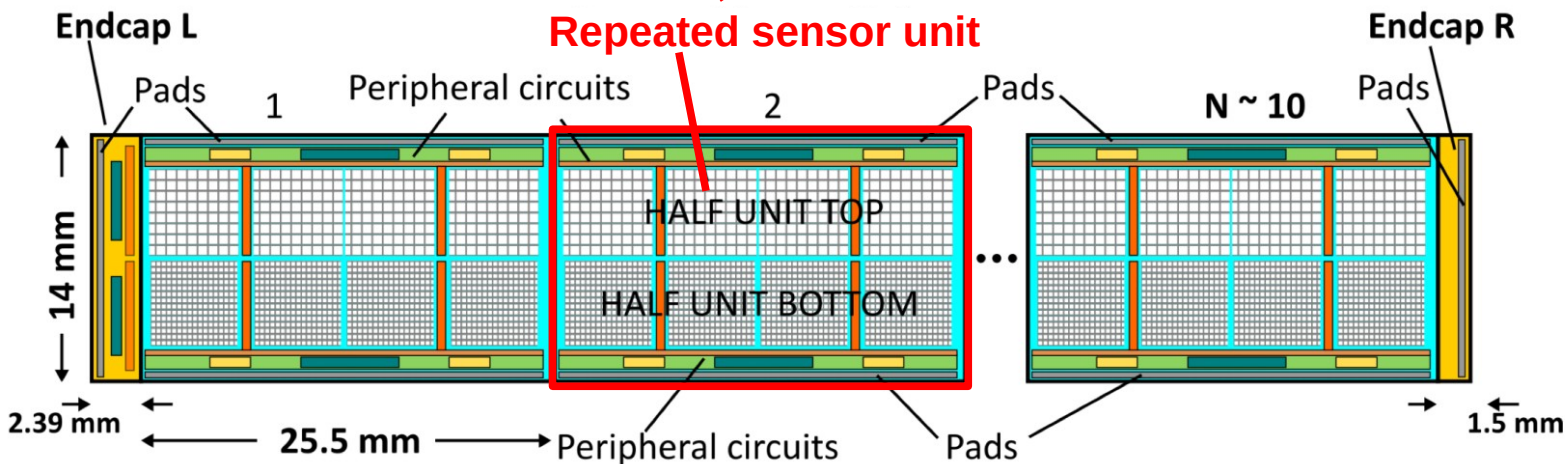
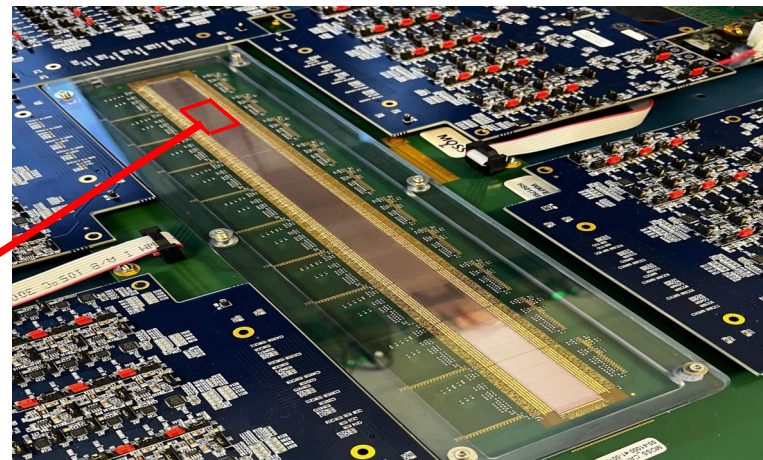
Summary

- Technology for ALICE ITS Inner Barrel upgrade for LHC Run 4:
large scale, bent monolithic active pixel sensors
- R&D :
 - Silicon flexibility and bending proved with routine bending tests
 - Bent and flat sensors have compatible performance
 - Sensors prototypes are radiation hard up to NIEL 10^{14} 1MeV n_{eq} cm^{-2}
 - Characterization of stitched sensors ongoing
 - Investigation of the air cooling and associated vibrations ongoing
- ITS3 R&D paves the way to thin, low-power sensors for the use in future ALICE3

Backup

Monolithic Stitched Sensor

- Size: 14 x 259 mm, 6.72 MPixel
- 10 Repeated sensor units
 - Top half unit pitch: $22.5 \times 22.5 \mu\text{m}^2$
 - Bottom half unit pitch $18 \times 18 \mu\text{m}^2$

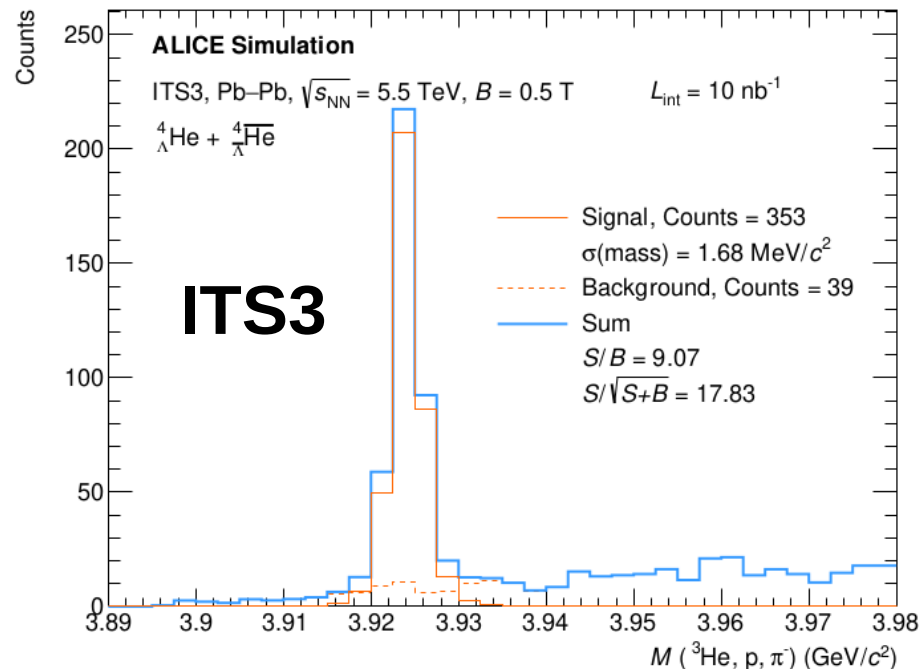
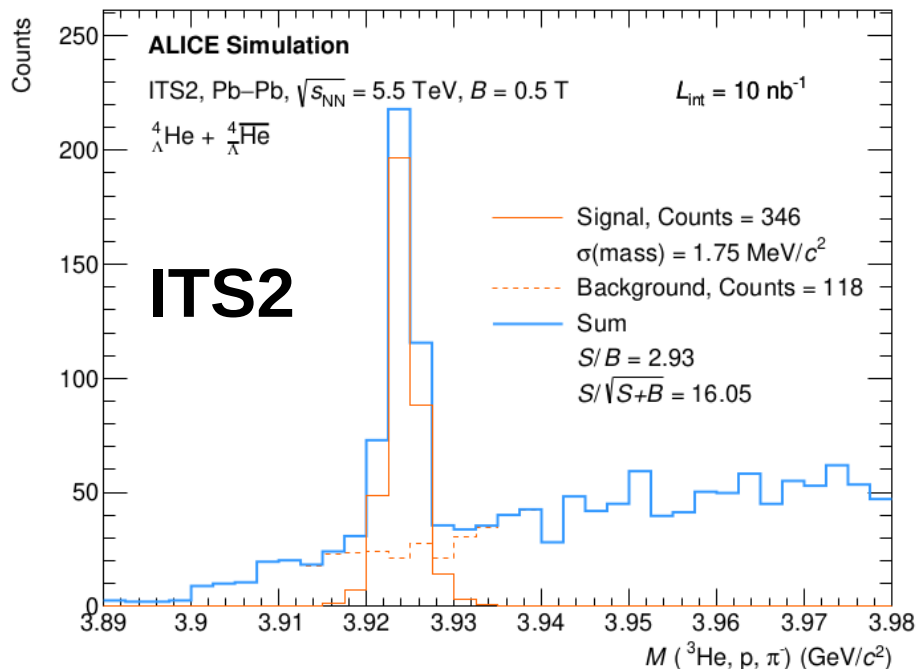


Reconstruction of hypernuclei with ITS3



ALICE-PUBLIC-2023-002

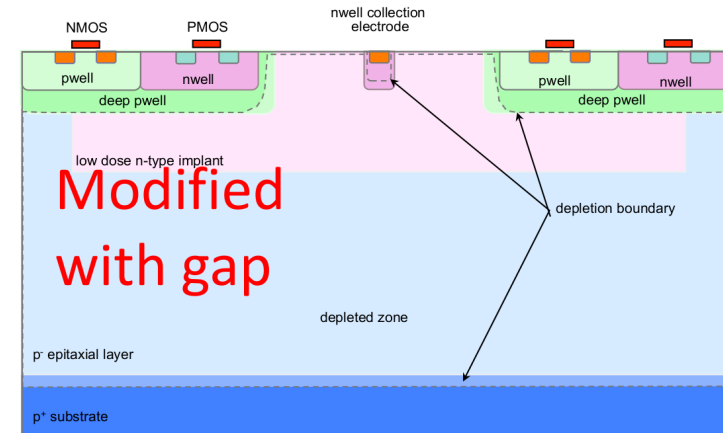
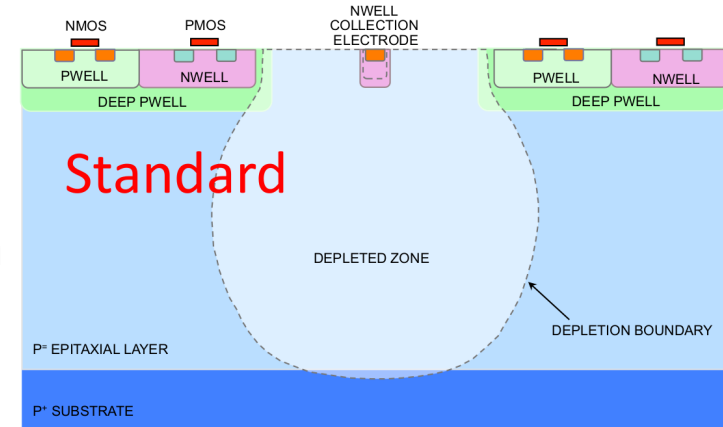
ITS3 improves impact parameter measurements of daughter ${}^3\text{He}$ decay



TPSCo 65 nm CMOS: benefits & features

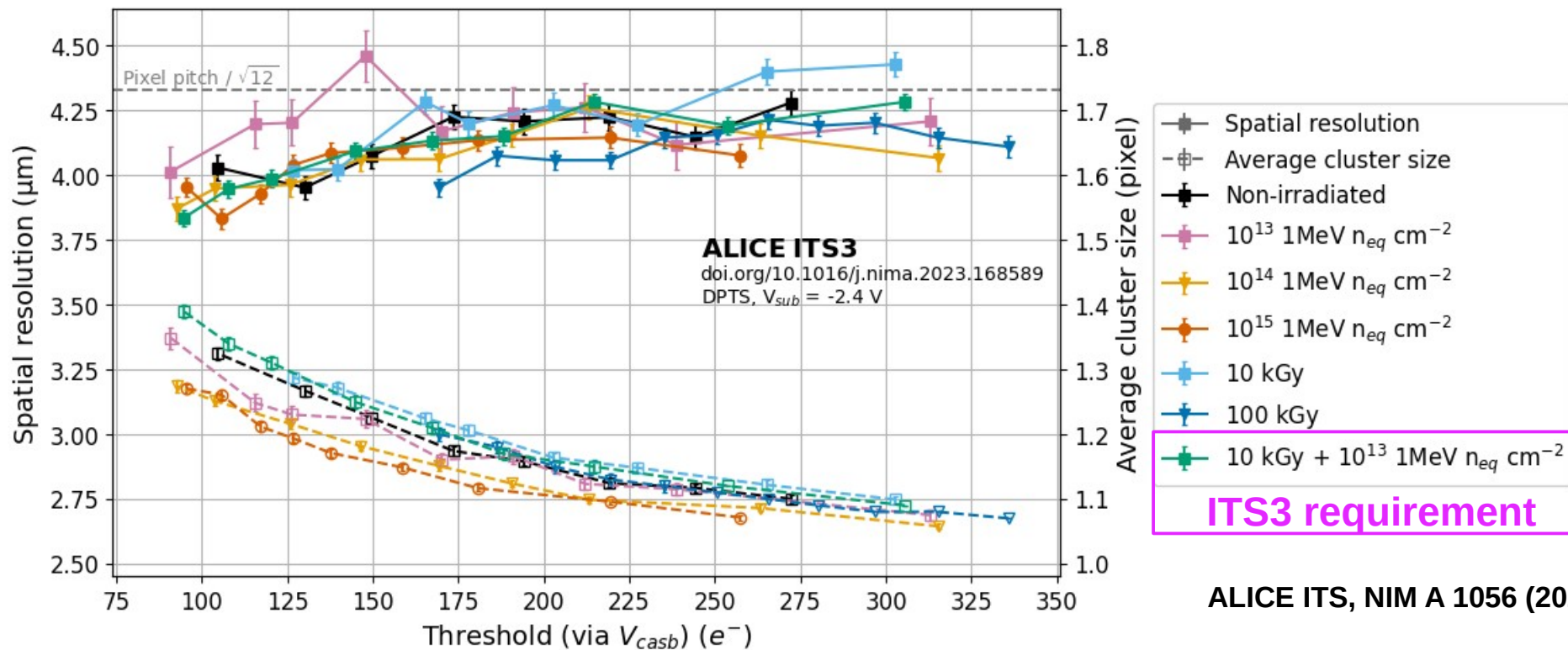
Tower Partners Semiconductor Company (TPSCo)

- **Benefits of 65 nm vs 180 nm**
 - smaller feature size \Rightarrow better spatial resolution
 - larger wafers: 300 mm vs 200 mm \Rightarrow final sensor $27 \times 9 \text{ cm}^2$
 - lower voltage : 1.2 vs 1.8 V \Rightarrow lower power consumption
 - thinner sensitive layer ($\sim 10 \mu\text{m}$) \Rightarrow lower material budget
- Provides 2D stitching
- 7 metal layers
- **Process modification for full depletion introduced:**
low dose n-type implant with gaps
 - reduces charge sharing
 - improves detection efficiency and speed



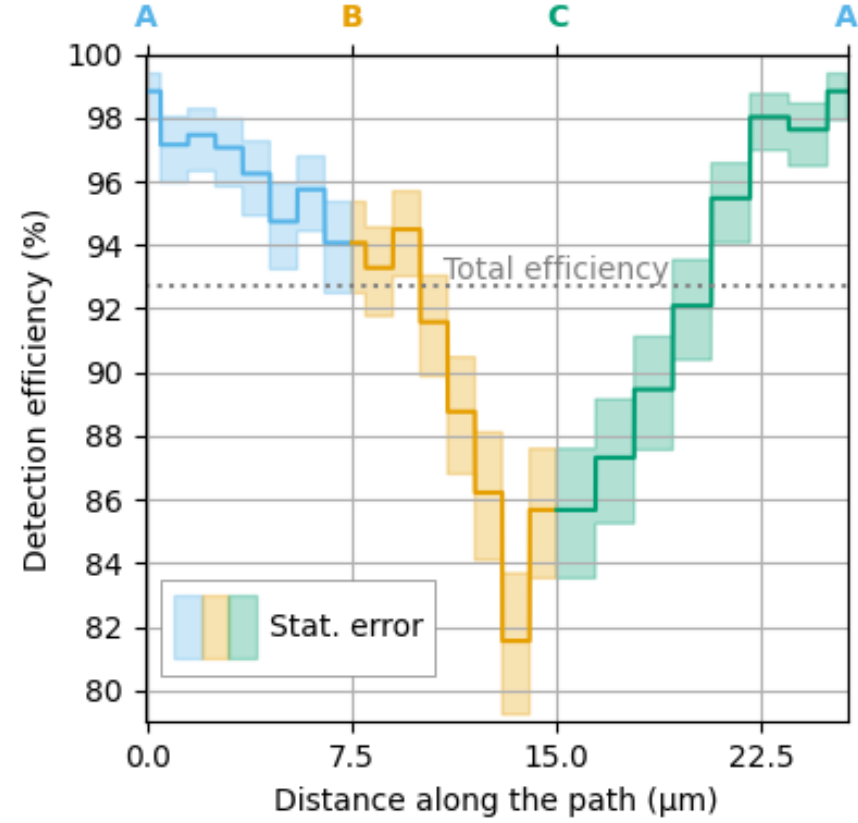
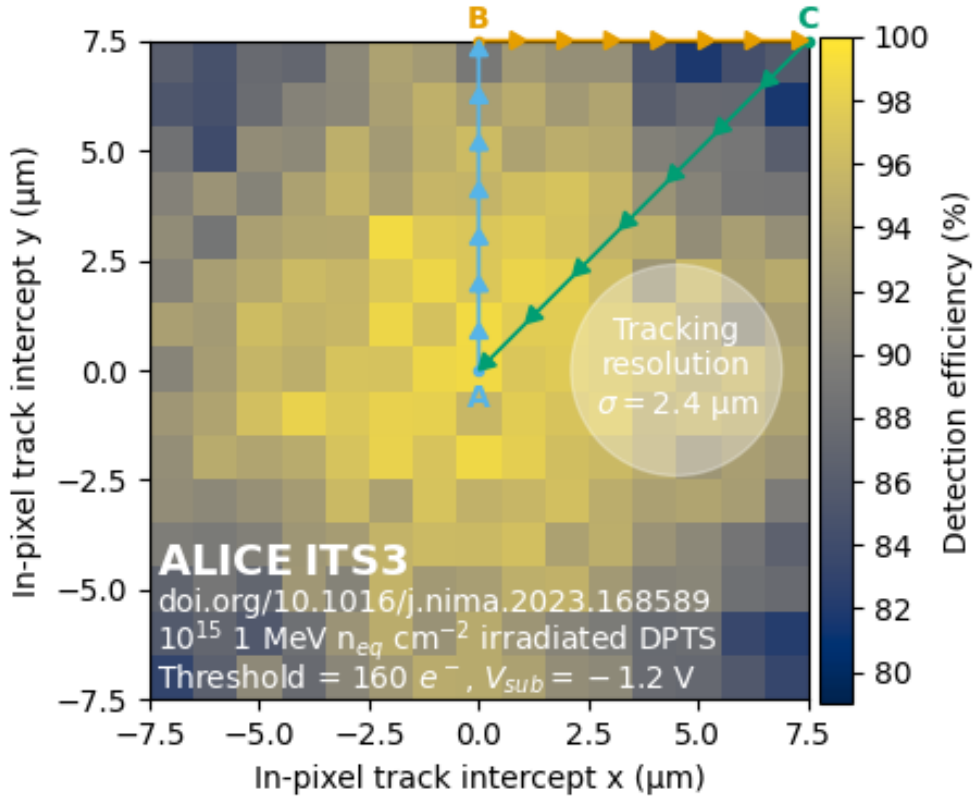
M. Munker et al 2019 JINST 14 C05013

DPTS – Spatial resolution after irradiation



Irradiation does not have strong impact on performance

DPTS in-pixel efficiency for irradiated sensor



10^{15} 1 MeV n_{eq} cm^{-2} irradiated sensor
160 eV threshold
10 GeV positive hadrons

Efficiency losses in pixel corners
due to charge sharing

ALICE ITS, NIM A 1056 (2023) 168589